

IN THE ABSTRACT

Please amend the Abstract as follows.

ABSTRACT OF THE DISCLOSURE

~~There is provided an electron beam wiring technique which can correct deflection for a micro field used in electron beam writing equipment with high precision.~~

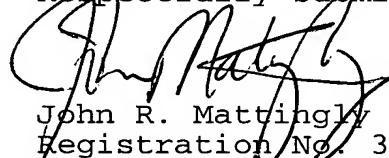
Electron beam writing equipment has an electron source; and an electron optics system irradiating for scanning an electron beam emitted from the electron source on a sample via deflection means having at least two different deflection speeds. and an An objective lens is used to form a desired pattern on the sample; a stage mounting the sample; a mark for beam correction provided on the stage; an electron detector detecting a backscattered electron, a secondary electron or a transmission electron obtained by irradiation of the electron beam; a function moving the The electron beam is moved by high speed scanning with the deflection means to repeat formation of a patterned beam.; a function moving the The electron beam is moved on the mark for beam correction by low speed scanning with the deflection means in synchronization with one cycle of the repetition.; and a function detecting a backscattered electron or a secondary electron emitted from the mark for beam

correction and near it by the low speed scanning or a transmission electron transmitted through the mark for beam correction to correct the The position or the deflection distance of the electron beam or blanking time is corrected using detectors for back scattered or secondary electrons from the detected result.

REMARKS

Examination is respectfully requested.

Respectfully submitted,



John R. Mattingly
Registration No. 30,293
Attorney for Applicants

MATTINGLY, STANGER & MALUR
1800 Diagonal Rd., Suite 370
Alexandria, Virginia 22314
(703) 684-1120
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